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Fig. 1

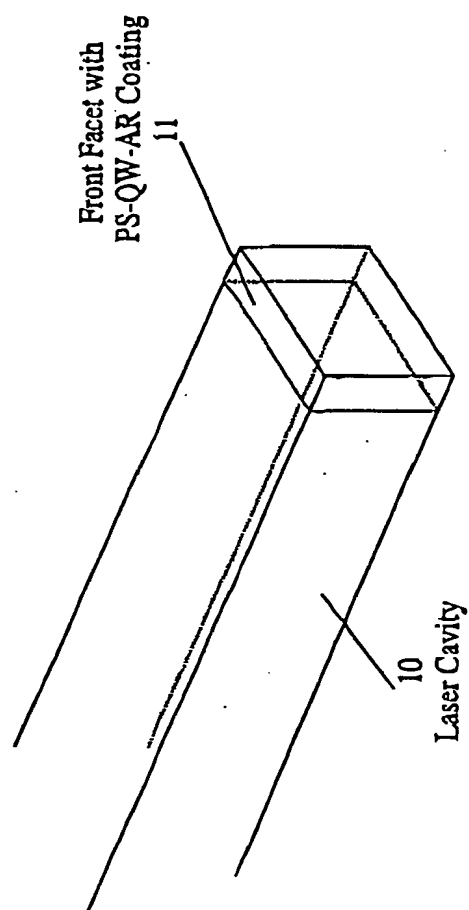


Fig. 2

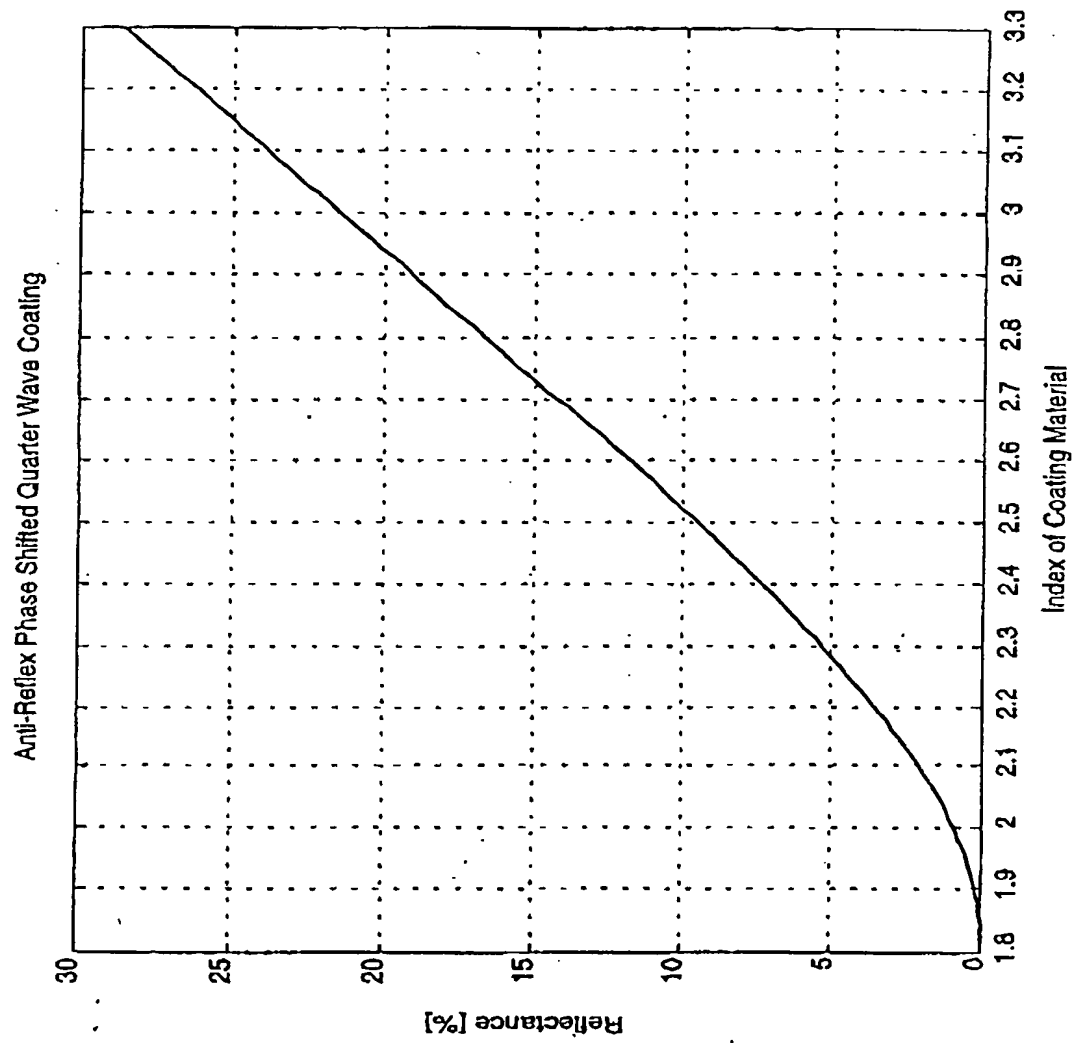


Fig. 3

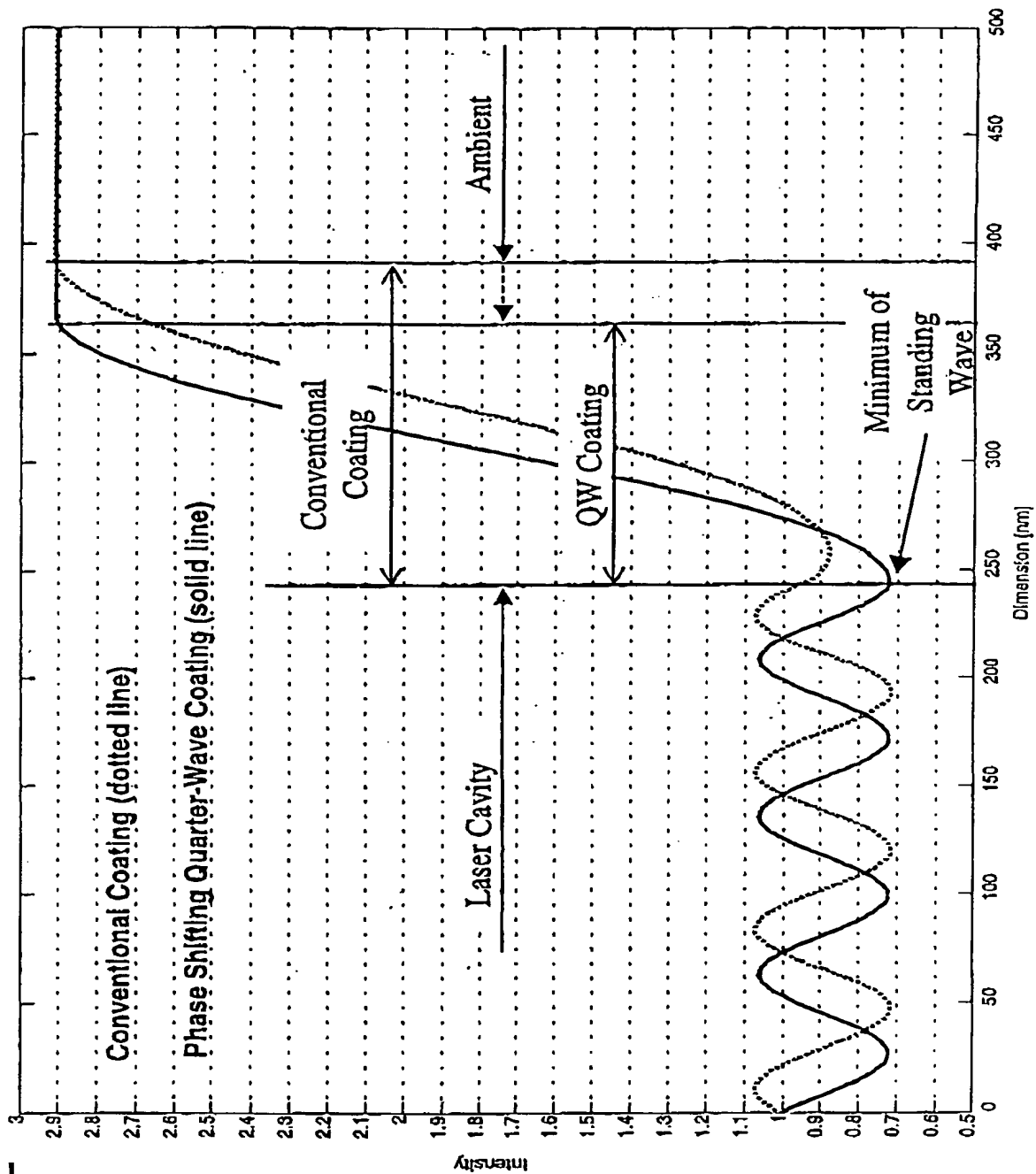


Fig. 4(a)

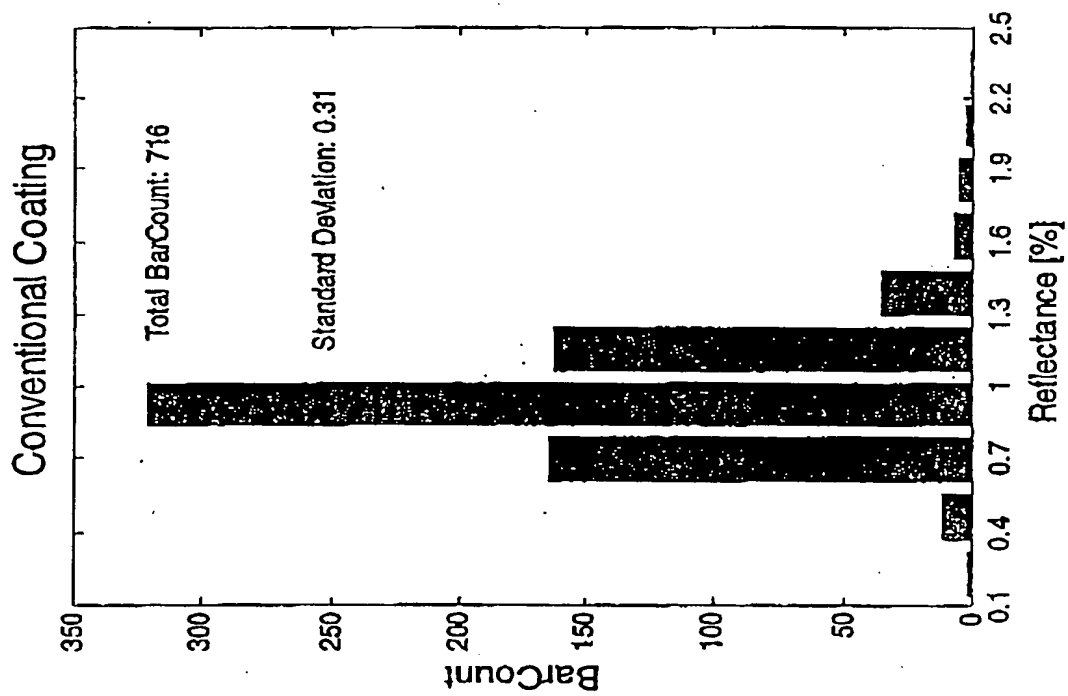


Fig. 4(b)

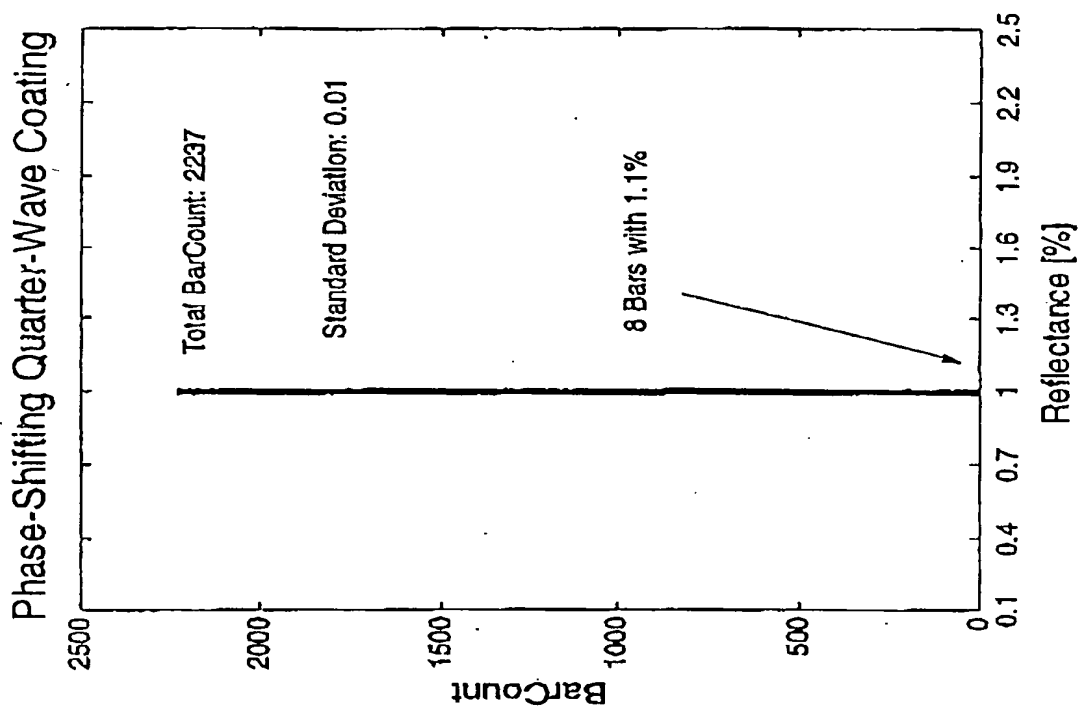
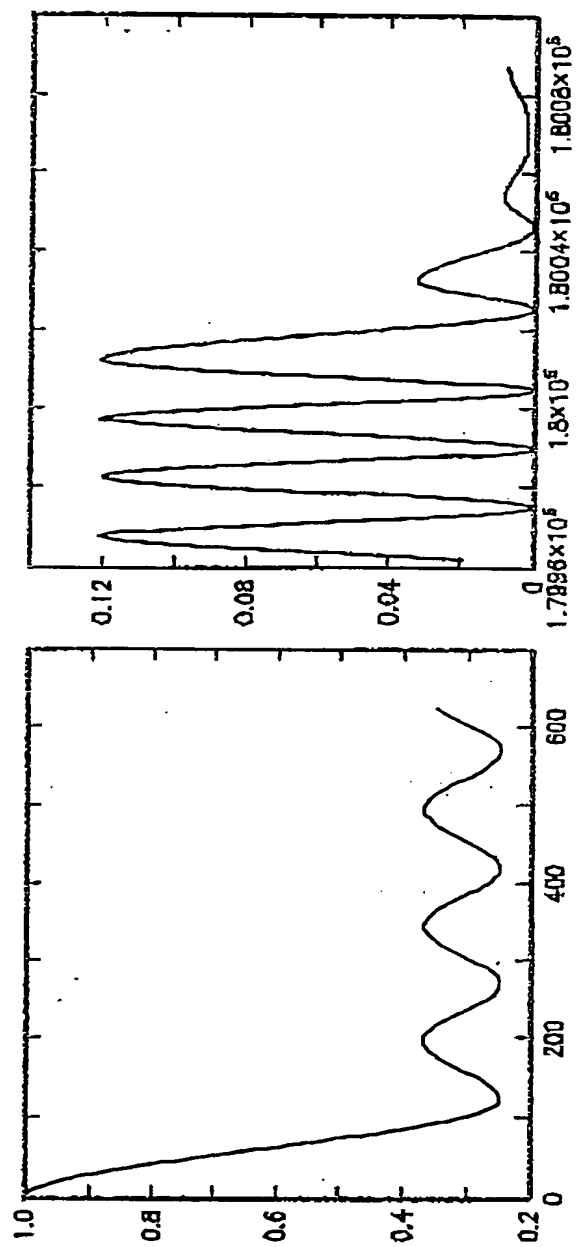
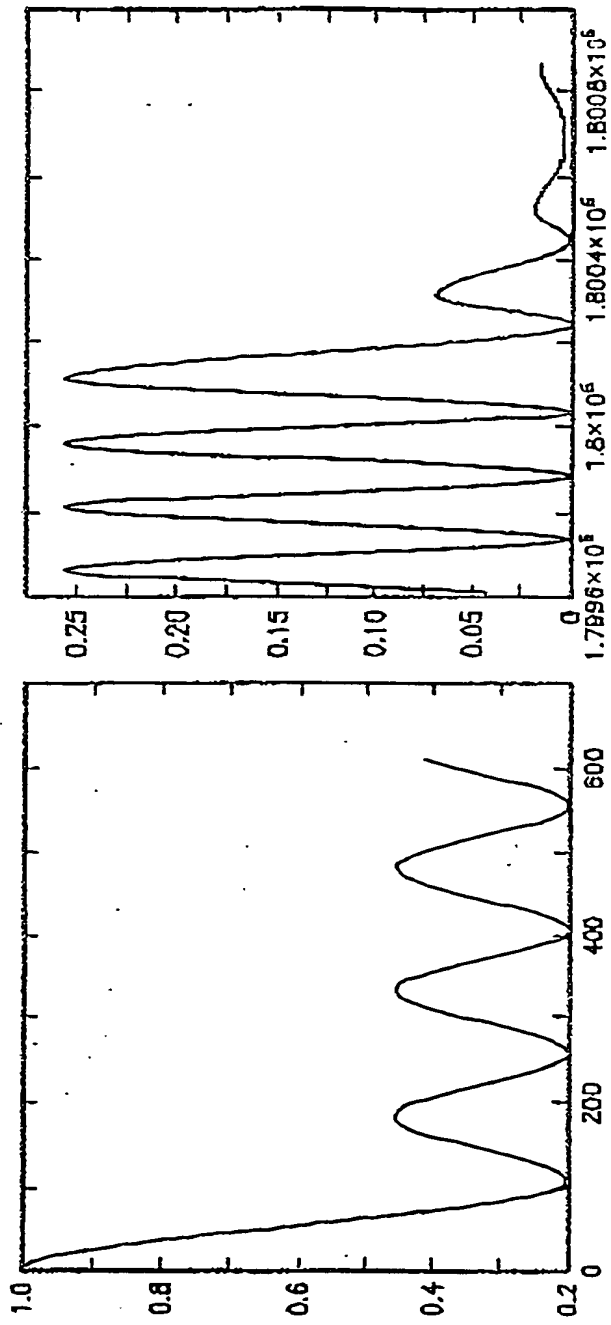


Fig. 5



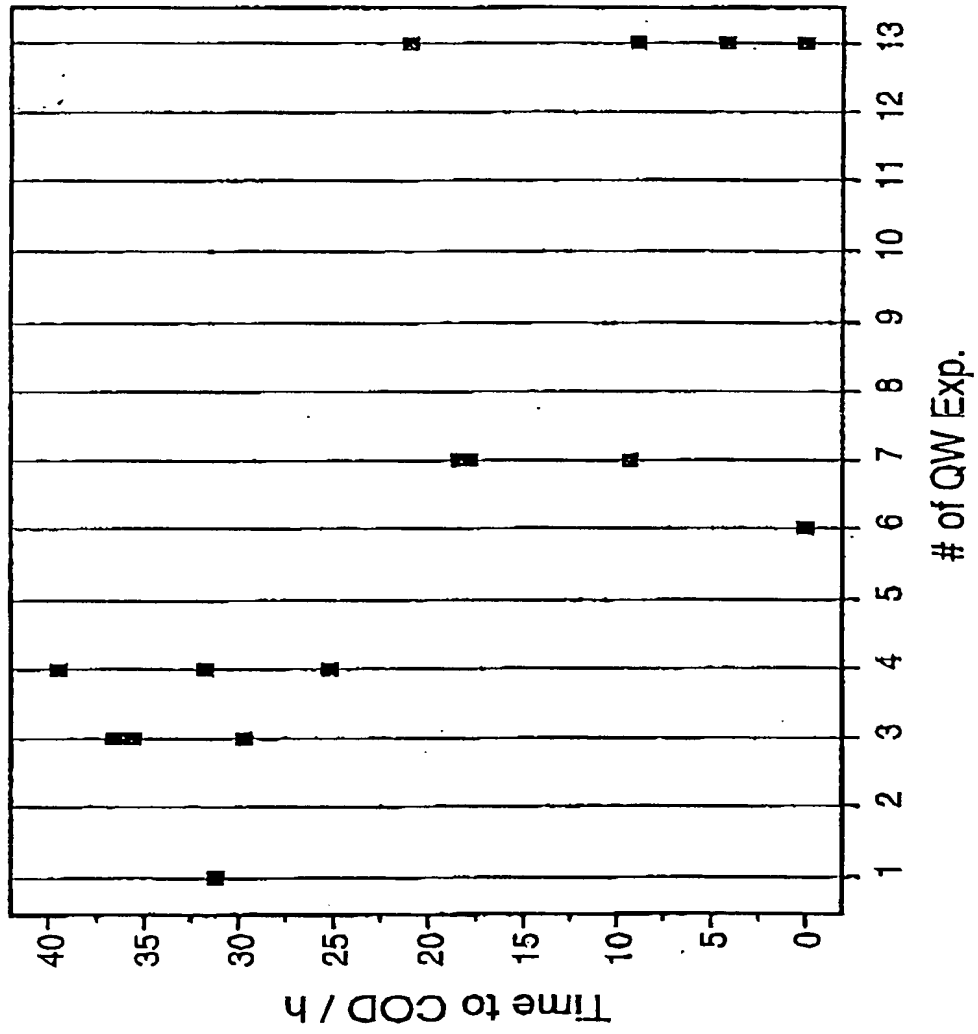
Phase Shifting Quarter Wave Coating with a 1 % Reflectance

Fig. 6



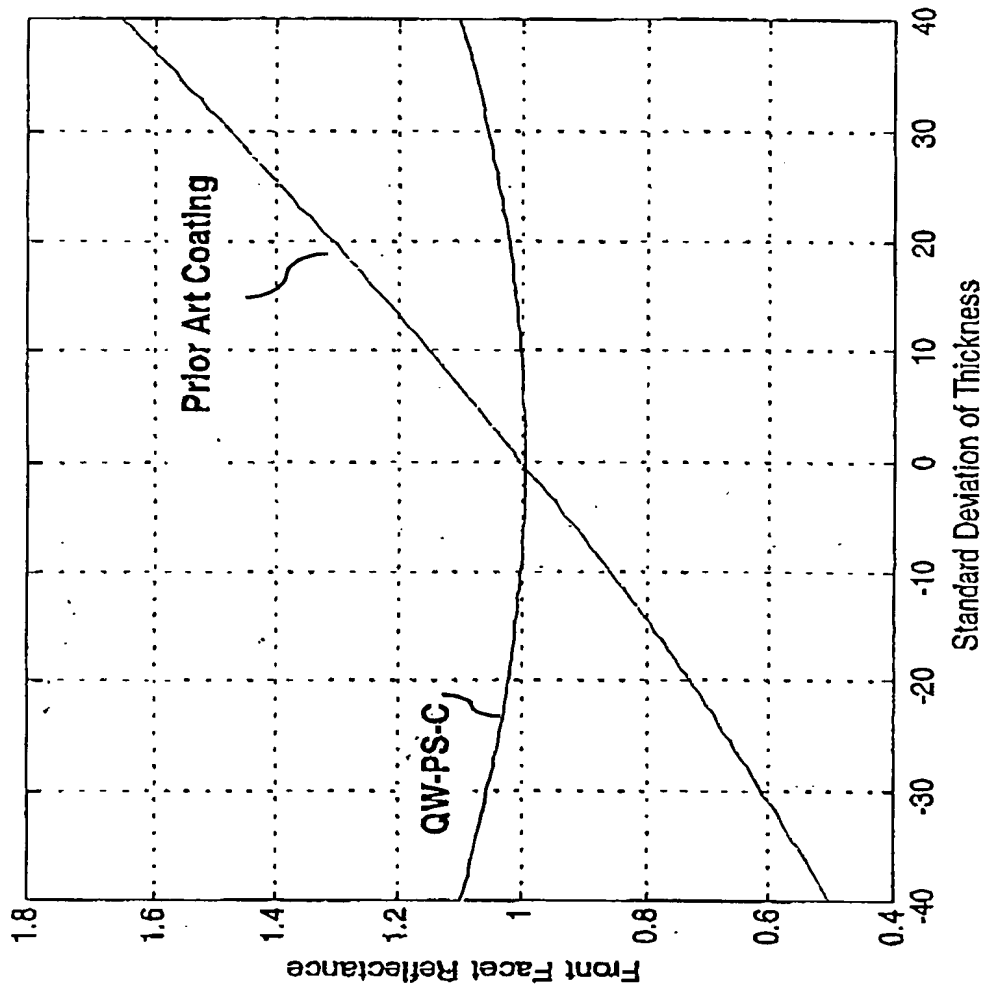
Phase Shifting Quarter Wave Coating with a 4 % Reflectance

Fig. 7



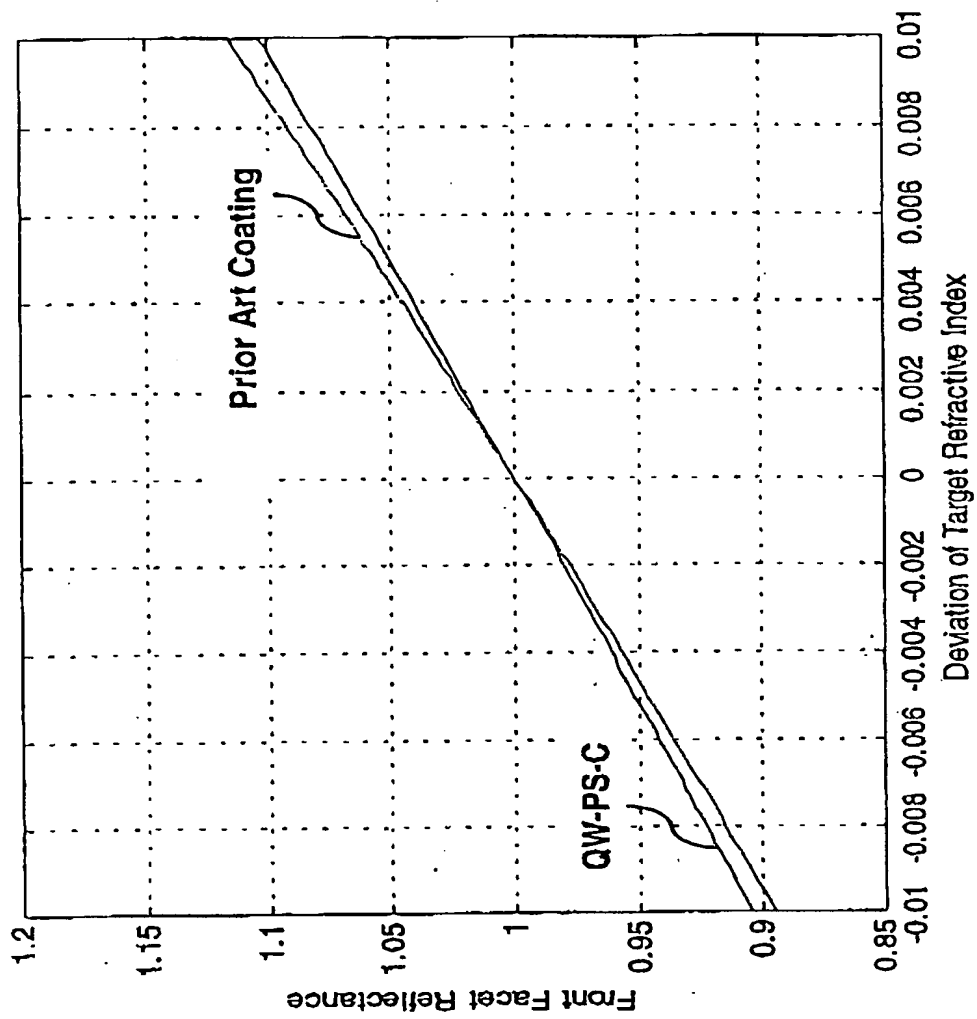
Time to COD vs. # of QW Exp

Fig. 8



Dependence of reflectance on thickness variation

Fig. 9



Dependence of Reflectance on index variation

Fig. 10

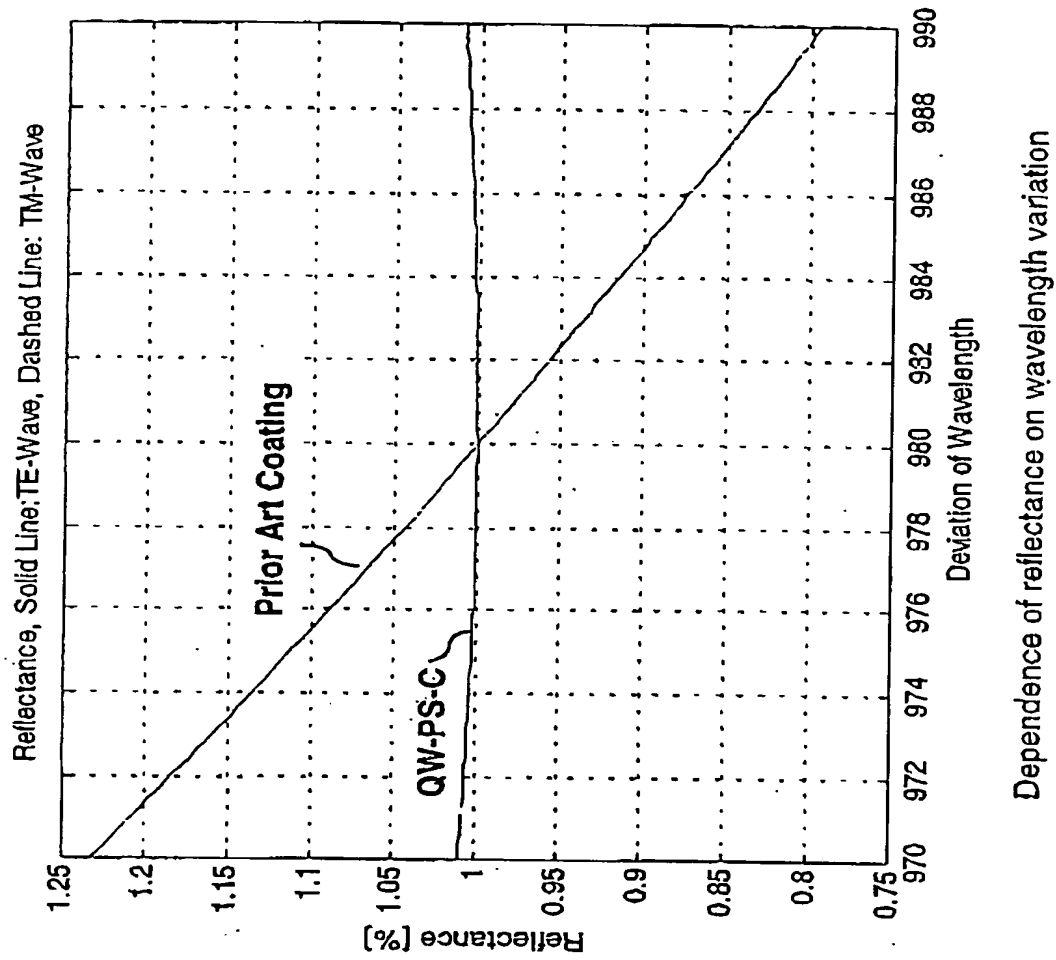


Fig. 11

Process parameters

Reflectivity R	index of refraction n	Substrate Temperature T_s (°C)	Pressure P (Torr)	Plasma Power L_{plasma} (W)	nitrogen flux η_{N_2} (sccm)	ammonia flux η_{NH_3} (sccm)	silane flux(*) η_{SiH_4} (sccm)
0.05%	1.86	300	1.4	25	35	18	236
1%	2.01	300	1.4	25	35	13	403
4%	2.23	300	1.4	25	35	8.5	491
1%(**)	1.83	300	1.4	20	330	11.2	300

(*) precursor gas of 2% SiH4 diluted in Helium

(**) conventional non- $\lambda/4$ coating

Fig. 12

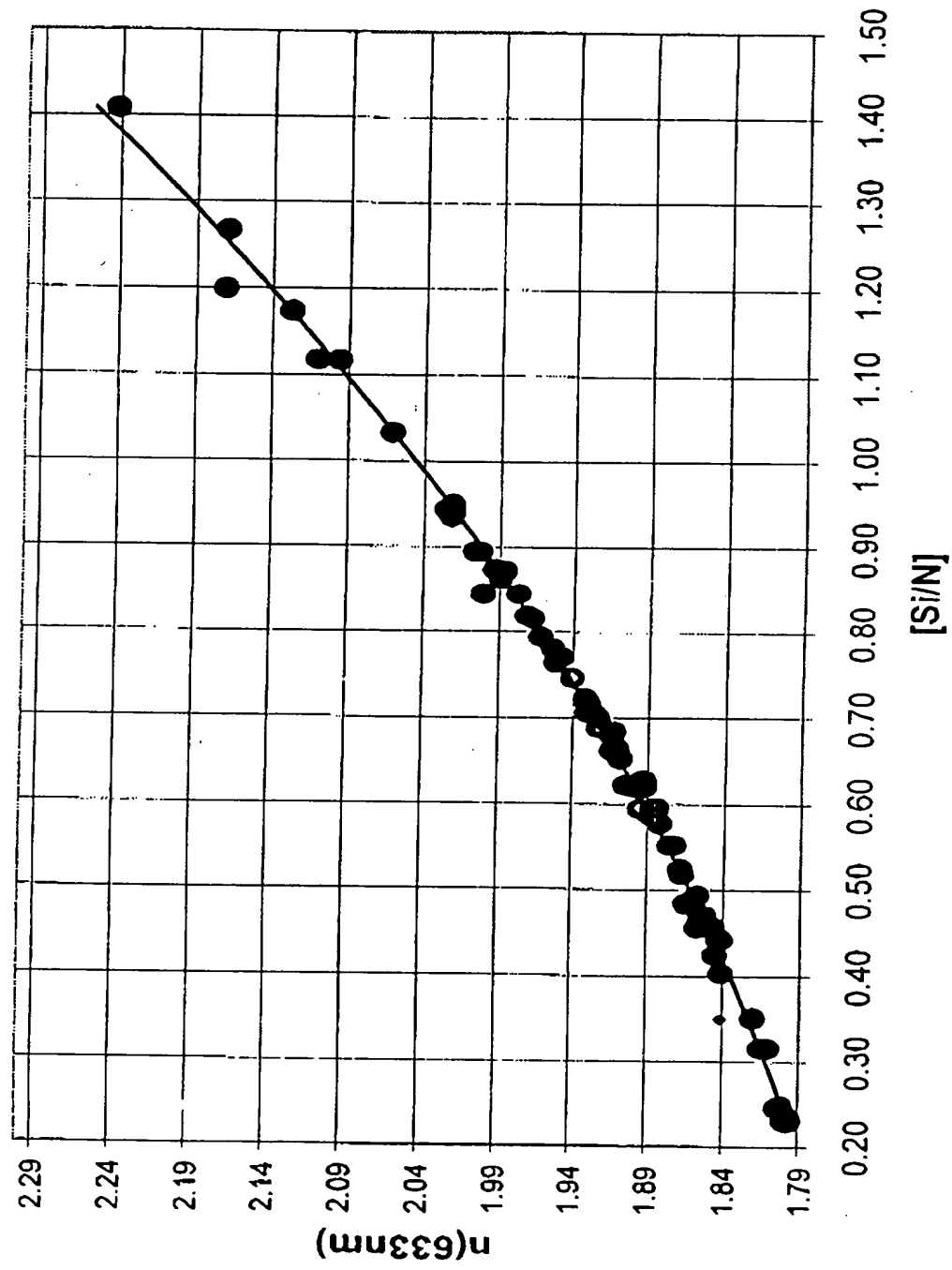


Fig. 13

